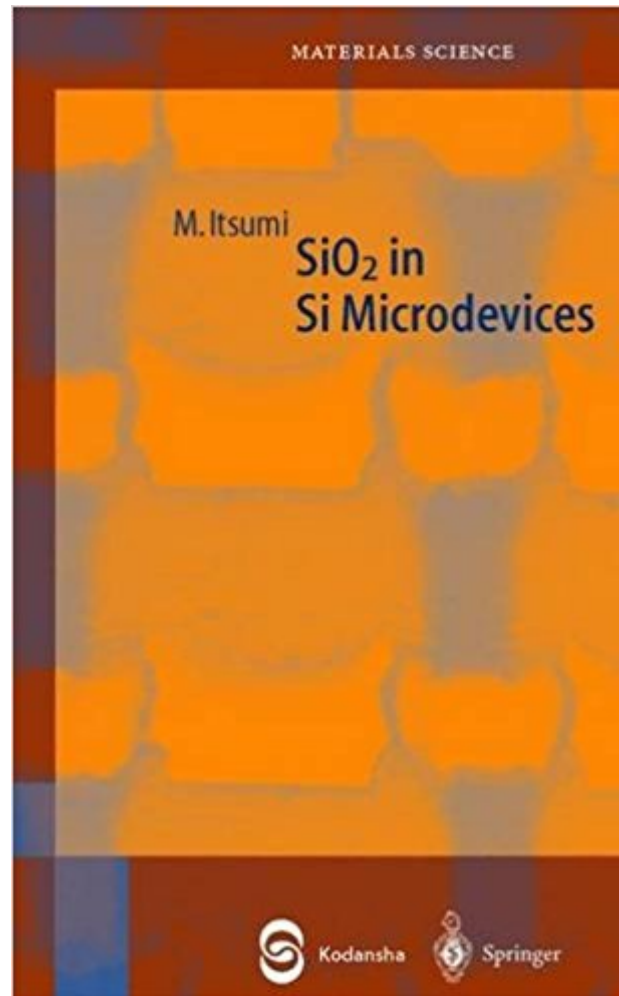




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# SiO<sub>2</sub> In Si Microdevices



## Synopsis

Electronic systems and digital computers are indispensable elements of modern multimedia technologies and the Internet society. But their explosive advance would not have been possible without the extraordinary progress in VLSI technology using high-quality SiO<sub>2</sub>. This volume addresses the thin gate oxides involved in the individual processes in fabrication, e.g. the growth, cleaning and thermal oxidation of silicon, metal interconnect formation, and photolithography. It describes new methods for observing defects in SiO<sub>2</sub> as well as novel approaches to eliminating such defects. The book will be a valuable resource for all materials scientists and engineers seeking to further advance the quality of silicon microdevices.

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